

METHOD AND APPARATUS FOR ADJUSTING THE THICKNESS OF A
THIN LAYER OF SEMICONDUCTOR MATERIAL

ABSTRACT

5 A method for adjusting the thickness of a thin
semiconductor material layer. The method includes
measuring the layer to establish a thickness profile,
determining thickness adjustment specifications from the
measured thickness profile, and adjusting the thickness
10 of the layer in accordance with the specifications by
sacrificial oxidation. An apparatus for adjusting the
thickness of a thin layer of semiconductor material
according to this method is also disclosed.

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